	Hits	Search Text	DBs
1		ETCHS3 and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM_TDB
2	853	ETCHS3 and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM_TDB
3	131	ETCHS3 and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (dop$ $2type)	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM_TDB
4	920	(ETCHS3 and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped)) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED)) and ETCHS3 near (dop$ $2type))	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM_TDB
5	175	((ETCHS3 and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped)) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED)) and ETCHS3 near (dop$ $2type)) and fluorine (F4 "CF sub 4") and chlorine HCl (CL2 "Cl sub 2")	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM_TDB
6	52	(((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si si con polysilicon doped) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED)) and ETCHS3 near (dop$ $2type)) and fluorine (F4 "CF sub 4") and chlorine HCl (CL2 "Cl sub 2")) and etch$3 same (fluorine (F4 "CF sub 4") same chlorine HCl (CL2 "Cl sub 2"))) and fluorine CF4 "CF sub 4" near chlorine HCl CL2	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM_TDB
7	167	(((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near si silicon polysilicon doped ((ETCHS3 and "SAME" EQUAL EQUIVALENT SIMILAR CLOSE NEAR (RATE SPEED) and ETCHS3 ... "CF sub 4" ... CL2 "Cl sub 2") and etch$3 same fluorine (F4 "CF sub 4") same chlorine HCl (CL2 "Cl sub 2"))	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM_TDB
8	55	((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED)) and ETCHS3 near (dop$ $2type)) and fluorine (F4 "CF sub 4") and chlorine HCl (CL2 "Cl sub 2")) and etch$3 same fluorine (F4 "CF sub 4") same chlorine HCl (CL2 "Cl sub 2"))) not ((((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED)) and ETCHS3 near (si silicon polysilicon doped)) (ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (dopos $2type) and fluorine (F4 "CF sub 4") and chlorine HCl (CL2 "Cl sub 2") and etch$3 same (fluorine (F4 "CF sub 4") same chlorine HCl (CL2 "Cl sub 2") and fluorine (F4 "CF sub 4") near (Cl) HCl (CL2 "Cl sub 2")))	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM_TDB
9	45	(((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped) ((ETCHS3 and "SAME" EQUAL EQUIVALENT SIMILAR CLOSE NEAR (RATE SPEED)) and ETCHS3 near (dopos $2type)) and fluorine (F4 "CF sub 4") and chlorine HCl (CL2 "Cl sub 2")) and etch$3 same fluorine (F4 "CF sub 4") same chlorine HCl (CL2 "Cl sub 2"))) and clear$3	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM_TDB
10	27	((((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED)) and ETCHS3 near (si silicon polysilicon doped) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED)) and ETCHS3 near dopos $2type) and fluorine (F4 "CF sub 4") and chlorine HCl (CL2 "Cl sub 2")) and clear$3) and ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED)) and ETCHS3 near (dopos $2type)) and fluorine (F4 "CF sub 4") and chlorine HCl (CL2 "Cl sub 2")) and etch$3 same fluorine (F4 "CF sub 4") same chlorine HCl (CL2 "Cl sub 2") and fluorine (F4 "CF sub 4") near (chlorine HCl CL2 "Cl sub 2")	US-PGPUB, EPO, JPO, DERWENT, IBM_TDB

	Hits	Search Text	DBs
11	18	((((ETCH$3 and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCH$3 near (si silicon polysilicon doped)) ((ETCH$3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCH$3 near (dopes $2type)) and (fluorine CF4 "CF sub 4") and (chlorine HCl CL2 "Cl sub 2")) and (etch$3 same (fluorine CF4 "CF sub 4") same (chlorine HCl CL2 "Cl sub 2")) and clean$3) and (((ETCH$3 and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCH$3 near (si silicon polysilicon doped)) ((ETCH$3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCH$3 near (dopes $2type)) and (fluorine CF4 "CF sub 4") and (chlorine HCl CL2 "Cl sub 2")) and (etch$3 same (fluorine CF4 "CF sub 4") same (chlorine HCl CL2 "Cl sub 2")) not ((((ETCH$3 and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCH$3 near (si silicon polysilicon doped)) ((ETCH$3 and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCH$3 near (dopes $2type)) and (fluorine CF4 "CF sub 4") and (chlorine HCl CL2 "Cl sub 2")) and (etch$3 same (fluorine CF4 "CF sub 4") same (chlorine HCl CL2 "Cl sub 2")) and ((fluorine CF4 "CF sub 4") near (chlorine HCl CL2 "Cl sub 2"))	USPAT US-PGPUB EPO JPO DERWENT IBM TDB
12	404	etch$3 same doped same undoped same rate	USPAT US-PGPUB EPO JPO DERWENT IBM TDB
13	5	(etch$3 same doped same undoped same rate) and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED)) and ((fluorine CF4 "CF sub 4") near (chlorine HCl CL2 "Cl sub 2"))	USPAT US-PGPUB EPO JPO DERWENT IBM TDB
14	5	(etch$3 same doped same undoped same rate) and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED)) and ((fluorine CF4 "CF sub 4") same (chlorine HCl CL2 "Cl sub 2")) not ((((etch$3 same doped same undoped same rate) and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED)) and ((fluorine CF4 "CF sub 4") near (chlorine HCl CL2 "Cl sub 2"))	USPAT US-PGPUB EPO JPO DERWENT IBM TDB
15	48	(etch$3 same doped same undoped same rate) and (("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))	USPAT US-PGPUB EPO JPO DERWENT IBM TDB